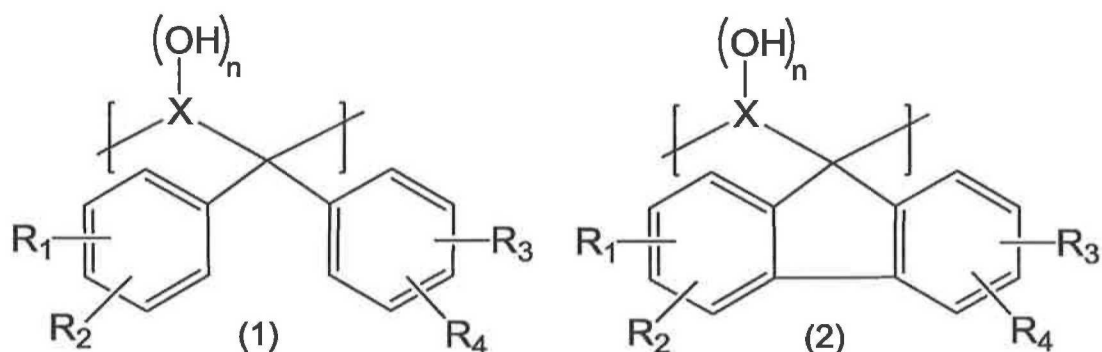


## ABSTRACT

## RESIST UNDERLAYER FILM-FORMING COMPOSITION

The present invention provides a novel resist underlayer film-forming composition capable of forming a resist underlayer film that has etching resistance and excellent  
 5 embeddability in a surface having concave portions and/or convex portions. A resist underlayer film-forming composition comprising a polymer having a structural unit represented by formula (1) or formula (2):



(wherein X is an arylene group, n is 1 or 2, and R<sub>1</sub>, R<sub>2</sub>, R<sub>3</sub>, and R<sub>4</sub> are each independently  
 10 a hydrogen atom, a hydroxy group, a C<sub>1-3</sub> alkyl group, or a phenyl group), and a solvent.

FIG. 1